

#7/Amend to  
Patent  
S/S/O  
PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Sun-oo KIM

Group Art Unit: 2823

Application No.: 09/739,743

Examiner: W. Coleman

Filed: December 20, 2000

For: METHOD FOR  
MANUFACTURING INTERLAYER  
DIELECTRIC LAYER IN A  
SEMICONDUCTOR DEVICE

Commissioner for Patents  
Washington, DC 20231

Sir:

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MAY - 1 2002  
TECHNOLOGY CENTER 2800

## AMENDMENT

In reply to the Office Action dated January 31, 2002, please amend the application as follows:

**IN THE CLAIMS:**

Please amend claims 1 and 7 as follows:

1. (Amended) A method for manufacturing an interlayer dielectric layer, the method comprising the steps of:

a) setting an active matrix provided with a substrate and interconnections formed on the substrate in a chamber;

FINNEGAN  
HENDERSON  
FARABOW  
GARRETT &  
DUNNER LLP

1300 I Street, NW  
Washington, DC 20005  
202.408.4000  
Fax 202.408.4400  
[www.finnegan.com](http://www.finnegan.com)